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MBMW-201: The next generation multi-beam mask writer (Conference Presentation) (Withdrawal Notice)

Christof Klein, Hans Loeschner, Elmar Platzgummer

Christof Klein, Hans Loeschner, Elmar Platzgummer, "MBMW-201: The next generation multi-beam mask writer (Conference Presentation) (Withdrawal Notice)," Proc. SPIE 10958, Novel Patterning Technologies for Semiconductors, MEMS/NEMS, and MOEMS 2019, 109580K (2 December 2019); doi: 10.1117/12.2516033

SPIE.

Event: SPIE Advanced Lithography, 2019, San Jose, California, United States

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Proc. SPIE 10958, 109580K (2019)

Online Publication Date: 16 August 2019

Withdrawn from Publication: 2 December 2019

Conference Date: 25 February-28 February 2019

Conference Location: San Jose, California, United States

Conference Title: Novel Patterning Technologies for Semiconductors, MEMS/NEMS and MOEMS 2019

Conference Chairs: Martha I. Sanchez

Publisher's Note: This video, originally published on 16 August 2019, was withdrawn per author request.

Novel Patterning Technologies for Semiconductors, MEMS/NEMS, and MOEMS 2019,
edited by Martha I. Sanchez, Eric M. Panning, Proc. of SPIE Vol. 10958, 109580K
© 2019 SPIE · CCC code: 0277-786X/19/\$18 · doi: 10.1117/12.2516033

Proc. of SPIE Vol. 10958 109580K-1